



Jung et al. 09/881,908 (TJK/182)
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of Parent et al.

Serial No.: 09/881,908

Filed: June 15, 2001

) HIGH DENSITY PLASMA PROCESSING
) APPARATUS
)
) Attorney Docket: TJK/182
)
) Group Art Unit: 1763
)
) Examiner: Luz Alejandro
)

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12/20/02
MW

Assistant Commissioner for Patents
Washington, D.C. 20231

AMENDMENT "A"

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Dear Sir:

This paper is filed in response to the Office Action mailed October 3, 2002 in connection with the above-designated application.

IN THE SPECIFICATION:

On page 10, lines 3-10, please delete the existing paragraph and replace it with the following paragraph:

Now, referring back to FIG. 1A, a heater 106, which applied heat to the atmosphere of the processing chamber 100, is fixed over the resonance antenna coil 102. This heater 106 can also surround the sidewalls of the processing chamber 100. The resonance antenna coil 102 is also connected to a antenna heating device 108 that lets a heat exchange medium flow into the insides of the hollow-tube antenna coil 102 in order to maintain the resonance antenna coil 102 at a temperature of 50 to 100 Celsius (C°). The heat exchange medium from the antenna heating device 108 circulates through the hollow-tube antenna coil 102 and then is emitted through a exhaust pipe 109 to the outside.